5. The synchronized pulsing arrangement of claim 4 wherein said pulse controlling subsystem is configured to generate at least a high level and a low level for said second RF signal, said high level and said low level governed by at least one value provided by said tool host computer.

6. The synchronized pulsing arrangement of claim 1 wherein said second RF signal, when pulsed, comprises at least a high pulse value and a low pulse value, wherein said low pulse value is non-zero.

7. The synchronized pulsing arrangement of claim 1 wherein said at least one parameter that reflects whether said first RF signal is pulsed high or pulsed low represents values obtained from a VI probe.

8. The synchronized pulsing arrangement of claim 1 wherein said at least one parameter that reflects whether said first RF signal is pulsed high or pulsed low represents an output impedance of said second RF generator.

9. The synchronized pulsing arrangement of claim 1 further comprising a match subsystem coupled to outputs of said first RF generator and said second RF generator, wherein said at least one parameter that reflects whether said first RF signal is pulsed high or pulsed low represents an impedance of an input of said match subsystem.

10. The synchronized pulsing arrangement of claim 1 wherein said second RF signal, when pulsed, comprises at least a predefined high pulse value and a predefined low pulse value.

11. The synchronized pulsing arrangement of claim 1 wherein said second RF signal, when pulsed, comprises at least a predefined high pulse value and a predefined low pulse value and wherein second RF signal transitions, after a predefined duration expires after being pulsed from said predefined low pulse value to said predefined high pulse value, to said predefined pulse low value.

detecting values of at least one parameter associated with said plasma processing chamber that reflects whether said first RF signal is pulsed high or pulsed low; and

pulsing a second RF signal, using a second RF generator, responsive to said detecting said values of said at least one parameter.

25. The method of claim 24 wherein said at least one parameter that reflects whether said first RF signal is pulsed high or pulsed low represents at least one of forward RF power and reflected RF power.

26. The method of claim 24 wherein said at least one parameter that reflect whether said first RF signal is pulsed high or pulsed low represents gamma, said gamma representing a numerical index indicating a degree of mismatch between reflected power and forward power of said second RF generator.

27. The method of claim 24 further comprising receiving a trigger threshold value from a tool host computer, said trigger threshold value to enable circuitry in said sensor subsystem of said second generator to ascertain whether said first RF signal is pulsed high or pulsed low.

28. The method of claim ~~24~~ 27 wherein said second RF signal comprises at least a high level and a low level when pulsed, said high level and said low level governed by at least one value provided by said tool host computer.

29. The method of claim 24 wherein said second RF signal, when pulsed, comprises at least a high pulse value and a low pulse value, wherein said low pulse value is non-zero.

30. The method of claim 24 wherein said at least one parameter that reflects whether said first RF signal is pulsed high or pulsed low represents values obtained from a VI probe.